國立中山大學 107 學年度碩士暨碩士專班招生考試試題

科目名稱:半導體概論【電機系碩士班甲組】

題號:431012

※本科目依簡章規定「可以」使用計算機(廠牌、功能不拘)(問答申論題)

共1頁第1頁

Dielectric constant: Si = 11.9; $SiO_2 = 3.9$. Bandgap: Si = 1.12 eV; GaAs = 1.42 eV.

- 1. A silicon sample has a doping profile with donors $N_D = N_O \exp(-mx)$. If $N_D >> n_i$, find the expression for the built-in electric field at equilibrium. (20%)
- 2. A Si p-n junction has same doping concentration 2×10^{16} cm⁻³ in each side. The peak electric filed in the junction at breakdown is 2×10^5 V/cm. Calculate the reverse breakdown voltage of this junction at 300K.
- 3. Calculate the oxide capacitance, the flatband capacitance, and the high frequency capacitance in inversion of a silicon MOS capacitor with a substrate doping $N_A = 2 \times 10^{17}$ cm⁻³, a 25 nm thick silicon dioxide and an aluminum gate ($\phi_M = 4.1 \text{ V}$).
- 4. For heterojunctions in the GaAs-AlGaAs system, the direct bandgap difference is accommodated approximately $\frac{2}{3}$ in the conduction band and $\frac{1}{3}$ in the valence band. The bandgap of AlGaAs is 1.85 eV if Al composition is 0.3. Draw the band diagrams of two heterojunctions:

 (a) N⁺-Al_{0.3}Ga_{0.7}As on n-GaAs (b) P⁺-Al_{0.3}Ga_{0.7}As on n-GaAs (20%).
- 5. In a metal-Si Schottky barrier contact, the barrier height is 0.85 eV and the effective Richardson constant is 110 A/K²-cm². Calculate the ratio of the injected hole current to the electron current at 300K. $D_p = 12 \text{ cm}^2/\text{s}$, $\tau_p = 5 \times 10^{-7} \text{ s}$, and $N_D = 2 \times 10^{16} \text{ cm}^{-3}$. (20%)